

This listing of claims will replace all prior versions of claims in the application.

Claims 1-36. (cancelled)

Claim 37. (currently amended) A photoresist composition that comprises:

(a) a photoacid generator compound; and

(b) a polymer that comprises a hydroxyadamantyl moiety, ~~a polymerized norbornene group~~ and at least two distinct repeat units that each has a photoacid-labile group.

Claim 38. (previously presented) The photoresist composition of claim 37 wherein the polymer comprises a lactone group.

Claim 39. (previously presented) The photoresist composition of claim 37 wherein the polymer comprises polymerized acrylate groups that comprise one or more photoacid-labile moieties.

Claim 40. (previously presented) The photoresist composition of claim 37 wherein the polymer comprises one or more nitrile moieties.

Claim 41. (cancelled)

Claim 42. (previously presented) The photoresist composition of claim 37 wherein the polymer is a terpolymer.

Claim 43. (previously presented) The photoresist composition of claim 37 wherein the polymer is a tetrapolymer.

Claim 44. (previously presented) The photoresist of claim 37 wherein the polymer is substantially free of aromatic groups.

Claim 45. (previously presented) The photoresist composition of claim 37 wherein the polymer is completely free of aromatic groups.

Claim 46. (previously presented) A microelectronic wafer substrate having coated thereon a layer of the photoresist composition of claim 37.

Claim 47. (new) A photoresist composition that comprises:
(a) a photoacid generator compound; and
(b) a polymer that comprises a hydroxyadamantyl moiety, a polymerized norbornene group and a lactone group.

Claim 48. (new) The photoresist composition of claim 47 wherein the polymer is at least substantially free of aromatic groups.

Claim 49. (new) The photoresist composition of claim 47 wherein the polymer comprises polymerized acrylate groups that comprise one or more photoacid-labile moieties.

Claim 50. (new) The photoresist composition of claim 47 wherein the polymer comprises one or more nitrile moieties.